## Tunable photodetectors via in situ thermal conversion of TiS<sub>3</sub> to TiO<sub>2</sub>

## Riccardo Frisenda

Foad Ghasemi, Andres Castellanos-Gomez

Instituto Madrileño de Estudios Avanzados en Nanociencia (IMDEA-nanociencia), Campus de Cantoblanco, E-28049 Madrid, Spain

Riccardo.frisenda@imdea.org

Low-dimensional semiconductors attracting the interest of the scientific community working on optoelectronic devices. These materials can be interesting to explore for band engineering given the large surface-volume ratio which gives the access to entire material modification. TiS<sub>3</sub> layered is a semiconductor which attracted much attention recently thanks to its stunning electronic and optoelectronic properties and its technologically relevant bandaap of 1.1 eV [1]. The layered nature of TiS<sub>3</sub> gives an easy route for the intercalation of oxygen allowing an efficient oxidation of the material. This process is accompanied by a large change in the material bandgap and structure [2].

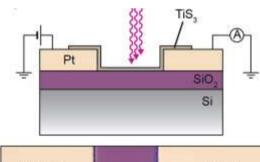
In this presentation we explore the possibility of thermally converting TiS3 nanoribbons to the oxide counterpart in a controlled way. We first study the oxidation of TiS<sub>3</sub> in powder form and for single nanoribbons deposited glass substrate. Usina spectroscopy and optical analysis we can monitor the material properties as a function of time while heating up to 350 °C. We find that an individual TiS3 nanoribbon converts to crystalline TiO<sub>2</sub> in approximately 15 minutes. Control experiments performed on TiS<sub>3</sub> nanoribbons fully encapsulated between hexagonal boron nitride flakes confirm the intercalation of oxygen leading the conversion process. After establishing the change in material properties we perform controlled oxidation of a TiS3 nanoribbon phototransistor. We monitor the change in current-voltage characteristics of

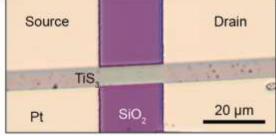
the device and in spectral photoresponse. The device, which in its pristine state has a frequency above 650 experiences a blue-shift reaching a final cutfrequency of 450 nm. **Various** intermediate states observed. are demonstrating the tunability of the material bandgap.

## References

- [1] Island, J.O., et al., TiS₃ transistors with tailored morphology and electrical properties, Advanced Materials, 2015, **27**: p. 2595.
- [2] lyikanat, F., et al., Vacancy formation and oxidation characteristics of single layer TiS<sub>3</sub>, J. Phys. Chem. C, 2015, **119**: p. 10709.

## **Figures**





**Figure 1:** Schematic of a TiS<sub>3</sub> photodetector (top) and optical microscope image of a real device (bottom).